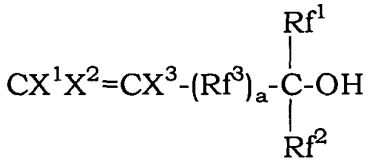
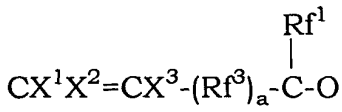
Abstract of the Disclosure

There are provided a fluorine-containing ethylenic monomer having hydroxyl group or fluoroalkyl carbonyl group and represented by the formula (1):



(1)

and the formula (14):



(14)

respectively, wherein X^1 and X^2 are the same or different and each is H or F; X^3 is H, F, Cl or CF_3; Rf^1 and Rf^2 are the same or different and each is a perfluoroalkyl group having 1 to 20 carbon atoms; Rf^3 is a fluorine-containing alkylene group having 1 to 40 carbon atoms or a fluorine-containing alkylene group having ether bond which has 1 to 100 carbon atoms and the sum of carbon atom and oxygen atom of two or more; a is 0 or 1, a fluorine-containing polymer having a structural unit of the above-mentioned monomer and a composition for a photoresist. The monomer has good polymerizability, particularly radical polymerizability, and the polymer obtained by polymerizing the monomer has excellent optical characteristics and is useful as a base polymer for an antireflection film and for a composition for a resist.